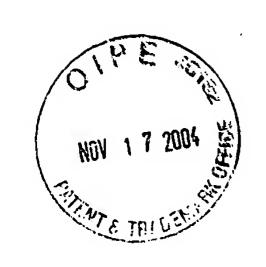
11-18-04





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LINDA E. HASTINGS

Any fee due as a result of this paper, not covered by an enclosed check, may be charged on Deposit Acct. No. 50-1290.

Attorney Docket No.: NECF 17.638B (100806-00233)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor:

Mami MIYASAKA

Serial No.:

10/657,429

Confirmation No.:

9031

Filed:

September 8, 2003

Title:

ELECTRON BEAM EXPOSURE MASK, ELECTRON BEAM

EXPOSURE METHOD, METHOD OF FABRICATING

SEMICONDUCTOR, AND ELECTRON BEAM EXPOSURE

APPARATUS

Examiner:

Anthony G. Quash

Group Art Unit:

2881

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

AMENDMENT UNDER 37 C.F.R. §1.312

SIR:

Pursuant to 37 C.F.R. §1.312, it is respectfully requested that the following amendment be entered, this amendment being filed before or on the date of payment of the Issue Fee: